

*IPU/A*



PATENT  
0171-1064P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Youichi OHSAWA et al. Conf.: 2846  
Appl. No.: 10/776,291<sup>r</sup> Group: 1752  
Filed: February 12, 2004 Examiner: John Chu  
For: NOVEL SULFONYLDIAZOMETHANES, PHOTOACID  
GENERATORS, RESIST COMPOSITIONS, AND  
PATTERNING PROCESS

REPLY UNDER 37 C.F.R. § 1.111

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

March 14, 2005

Sir:

In reply to the Office Action dated December 14, 2004, the following remarks and Terminal Disclaimer are respectfully submitted in connection with the above-identified application.

This reply includes Remarks and Terminal Disclaimer.